

Atty. Docket No. OPP 031047 US

IN THE UNITED STATES PATENT & TRADEMARK OFFICE

IN RE APPLICATION OF:

:

Jae-Won HAN

: GROUP ART UNIT:

SERIAL NO: NEW APPLICATION

:

FILED: HEREWITH

: EXAMINER:

FOR: Method for Manufacturing Silicide and Semiconductor with the Silicide

I hereby certify that this document is being deposited with the United States Postal Service as Express Mail No.

ER 189265931US in an envelope addressed to Commissioner for Patents, Washington, D.C. 20231,
on December 30, 2003.

By:


Jennie Heaton

REQUEST FOR PRIORITY UNDER 35 U.S.C. 119(a)-(b) AND 37 C.F.R. 1.55

COMMISSIONER FOR PATENTS
WASHINGTON, D.C. 20231

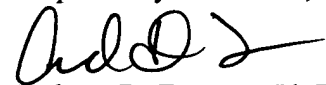
SIR:

Applicant respectfully requests under the Paris Convention for the Protection of
Intellectual Property the benefit of the filing date of the prior foreign application(s) identified
below:

<u>Serial No.</u>	<u>Filing Date</u>	<u>Country of Filing</u>
10-2003-0021958	April 8, 2003	Republic of KOREA

A certified copy of the priority application will be filed before any U.S. patent issues
from the above-captioned application.

Respectfully submitted,



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